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(21)Application number :	10-182641	(71)Applicant : TOSHIBA CORP
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(54) POLYMER FOR PHOTOSENSITIVE COMPOSITION AND PATTERN FORMING METHOD USING IT

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a photosensitive composition, excellent in light transmissivity, excellent in dry-etching tolerance, high in reaction efficiency by an acid catalyst, and excellent in adhesiveness to a substrate, and a pattern forming method giving an excellent pattern shape.

SOLUTION: This photosensitive composition includes an optical acid- producing agent and a copolymer having molecular-weight distribution given by the ratio M_w/M_n of weight-average molecular weight M_w to number-average molecular weight M_n of 1.0 to 1.4 and obtained by living-polymerizing a vinyl monomer having an alicyclic skeleton or a naphthalene skeleton, and/or a (meta) acrylic ester monomer, and this pattern forming method is for developing a photosensitive material using the same by exposing it to light of short wavelengths.

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